

**AMENDMENTS TO THE SPECIFICATION:**

*Please amend the paragraph at page 11, line 17, as follows:*

These hydrocarbon groups in R<sup>7</sup> and R<sup>8</sup> may further have a substituent(s).

When the alkyl group R<sup>7</sup> and R<sup>8</sup> has a substituent, the substituted alkyl group is constituted by binding a ~~substituent~~ substituent and an ~~alkylene~~ alkylene group, and a monovalent non-metallic atomic group except a hydrogen atom is used as the substituent. Preferred examples of the monovalent groups include a halogen atom(F, Br, Cl, I), a hydroxyl group, an alkoxy group, an aryloxy group, a mercapto group, an alkylthio group, an arylthio group, an alkyldithio group, an aryldithio group, an amino group, an N-alkylamino group, an N,N-diarylarnino group, an N-alkyl-N-arylamino group, an acyloxy group, a carbamoyloxy group, an N-alkylcarbamoyloxy group, an N-arylcarbamoyloxy group, an N,N-dialkylcarbamoyloxy group, an N,N-diarylcarbamoyloxy group, an N-alkyl-N-arylcarbamoyloxy group, an alkylsulfoxy group, an arylsulfoxy group, an acylthio group, an acylamino group, an N-alkylacylarnino group, an N-acrylacylarnino group, a ureido group, an N'-alkylureido group, an N',N'-dialkylureido group, an N'-arylureido group, an N',N'-diarylureido group, an N'-alkyl-N'-arylureido group, an N-alkylureido group, an N-arylureido group, an N'-alkyl-N-alkylureido group, an N'-alkyl-N-arylureido group, an N',N'-dialkyl-N-alkylureido group, N',N'-dialkyl-N-arylureido group, an N'-aryl-N-alkylureido group, an N'-aryl-N-arylureido group, an N',N'-diaryl-N-alkylureido group, an N'-alkyl-N'-aryl-N-alkylureido group, an N'-alkyl-N'-aryl-N-arylureido group, an alkoxycarbonylamino group, an aryloxycarbonylamino group, an N-alkyl-N-alkoxycarbonylamino group, an N-alkyl-N-aryloxycarbonylamino group, an N-aryl-N-alkoxycarbonylamino group, an N-aryl-N-aryloxycarbonylamino

group, a formyl group, an acyl group, a carboxyl group, an alkoxy carbonyl group, an aryloxy carbonyl group, a carbamoyl group, an N-alkyl carbamoyl group, an N-dialkyl carbamoyl group, an N-aryl carbamoyl group, an N,N-diaryl carbamoyl group, an N-alkyl-N-aryl carbamoyl group, an alkylsulfinyl group, an arylsulfinyl group, an alkylsulfonyl group, an arylsulfonyl group, a sulfo group (-SO<sub>3</sub>H) and a conjugate base group thereof (hereinafter referred to as "a sulfonato group"), an alkoxy sulfonyl group, an arylsulfonyl group, a sulfinamoyl group, an N-alkylsulfinamoyl group, an N,N-dialkylsulfinamoyl group, an N-arylsulfinamoyl group, an N,N-diarylsulfinamoyl group, an N-alkyl-N-arylsulfinamoyl group, a sulfamoyl group, an N-alkylsulfamoyl group, an N,N-dialkylsulfamoyl group, an N-arylsulfamoyl group, an N,N-diarylsulfamoyl group, an N-alkyl-N-arylsulfamoyl group, a phosphono group (-PO<sub>3</sub>H<sub>2</sub>) and a conjugate base group thereof (hereinafter referred to as "a phosphonato group"), a dialkylphosphono group (-PO<sub>3</sub>(alkyl)<sub>2</sub>), a diarylphosphono group (-PO<sub>3</sub>(alkyl)<sub>2</sub>), an alkylarylphosphono group (-PO<sub>3</sub>(alkyl)(aryl)), a monoalkylphosphono group (-PO<sub>3</sub>H(alkyl)) and a conjugate base group thereof (hereinafter referred to as "an alkylphosphonato group"), a monoarylphosphono group (-PO<sub>3</sub>H(aryl)) and a conjugate base group thereof (hereinafter referred to as "an arylphosphonato group"), a phosphonoxy group (-OPO<sub>3</sub>H<sub>2</sub>) and a conjugate base group thereof (hereinafter referred to as "a phosphonatoxy group"), a dialkylphosphonoxy group (-OPO<sub>3</sub>(alkyl)<sub>2</sub>), a diarylphosphonoxy group (-OPO<sub>3</sub>(aryl)<sub>2</sub>), an alkylarylphosphonoxy group (-OPO<sub>3</sub>(alkyl)(aryl)), a monoalkylphosphonoxy group (-OPO<sub>3</sub>H(alkyl)) and a conjugate base group thereof (hereinafter referred to as "an alkylphosphonatoxy group"), a monoarylphosphonoxy group (-OPO<sub>3</sub>H(aryl)) and a conjugate base group thereof (hereinafter referred to as

"an arylphosphonatoxy group), a cyano group, a nitro group, an aryl group, an alkenyl group and an alkynyl group.

*Please amend the paragraph at page 15, line 24, as follows:*

Further, the monovalent group as R<sup>7</sup> and R<sup>8</sup> each may be a substituted alkyl group. Examples of an alkylene moiety in such a substituted alkyl group include divalent organic residues formed by removing one hydrogen atom from each of the C1-20 alkyl groups as recited above, preferably C1-12 straight-chain alkylene groups, C3-12 branched alkylene groups and C5-10 cycloalkylene groups. Suitable examples of a substituted alkyl group formed by combining a substituent and an alkylene group include chloromethyl, bromomethyl, 2-chloroethyl, trifluoromethyl, methoxymethyl, methoxyethoxyethyl, allyloxymethyl, phenoxyethyl, methylthiomethyl, tolylthiomethyl, ethylaminoethyl, diethylaminopropyl, morpholinopropyl, acyloxymethyl, benzoyloxymethyl, N-cyclohexylcarbamoyloxyethyl, N-phenylcarbamoyloxyethyl, acetylaminoethyl, N-ethylbenzoylaminopropyl, 2-hydroxyethyl, 2-hydroxypropyl, carboxypropyl, methoxycarbonylethyl, allyloxycarbonylbutyl, chlorophenoxy carbonylmethyl, carbamoylmethyl, N-methylcarbamylethyl, N,N-dipropyl-carbamoylmethyl, N-(methoxyphenyl)carbamoylethyl, N-methyl-N-(sulfophenyl)carbamoylmethyl, sulfobutyl, sulfonatobutyl, sulfamoylbutyl, N-ethylsulfamoylmethyl, N,N-dipropylsulfamoylpropyl, N-tolylsulfamoylpropyl, N-methyl-N-(phosphonophenyl)sulfamoyloctyl, phosphonobutyl, phosphonatohexyl, diethylphosphonobutyl, diphenylphosphono-propyl, methylphosphonobutyl, methylphosphonatobutyl, triphosphonohexyl, tolylphosphonatohexyl, phosphonoxy-

propyl, phosphonatoxybutyl, benzyl, phenetyl phenethyl  $\alpha$ -methylbenzyl, 1-methyl-1-phenylethyl, p-methylbenzyl, cinnamyl, allyl, 1-propenylmethyl, 2-but enyl, 2-methylallyl, 2-methyl-propenylmethyl, 2-propenyl, 2-butynyl and 3-butynyl groups.

*Please amend the paragraph at page 55, line 22, as follows:*

Specific examples of the acid generator include onium salts such as: the diazonium salts described in S.I. Schlesinger, *Photogr. Sci. Eng.*, 18, 387 (1974) and T.S. Bal et al., *Polymer*, 21, 423 (1980); the ammonium salts described in U.S. Patents 4,069,055 and 4,069,056 and Japanese Patent Laid-Open No. 140,140/1991; the phosphonium salts described in D.C. Necker et al., *Macromolecules*, 17, 2468 (1984), C.S. Wen et al., *Teh, Proc. Conf. Rad. Curing ASIA*, p.478 Tokyo, Oct. (1988), and U.S. Patents 4,069,055 and 4,069,056; the iodonium salts described in J.V. Crivello et al., *Macromolecules Macromolecules* 10 (6), 1307 (1977), *Chem. & Eng. News*, Nov. 28, p.31 (1988), European Patent 104,143, U.S. Patents 339,049 and 410,201, and Japanese Patent Laid-Open Nos. 150,848/1990 and 296,514/1990; the sulfonium salts described in J.V. Crivello et al., *Polymer J.*, 17, 73 (1985), J.V. Crivello et al., *J. Org. Chem.*, 43, 3055 (1978), W.R. Watt et al., *J. Polymer Sci., Polymer Chem. Ed.*, 22, 1789 (1984), J.V. Crivello et al., *Polymer Bull.*, 14, 279 (1985), J.V. Crivello et al., *Macromolecules*, 14 (5), 1141 (1981), J.V. Crivello et al., *J. Polymer Sci., Polymer Chem. Ed.*, 17, 2877 (1979), European Patent 370,693, U.S. Patent 3,902,114, European European Patents 233,567, 297,443, and 297,442, U.S. Patents 4,933,377, 410,201, 339,049, 4,760,013, 4,734,444, and 2,833,827, and German Patents 2,904,626, 3,604,580, and 3,604,581; the selenonium salts described in J.V. Crivello et al.,

*Macromolecules*, 10 (6), 1307 (1977) and J.V. Crivello et al., *J. Polymer Sci.*, *Polymer Chem. Ed.*, 17, 1047 (1979); and the arsonium salts described in C.S. Wen et al., *Teh, Proc. Conf. Rad. Curing ASIA*, p.478 Tokyo, Oct. (1988). Examples thereof further include the organohalogen compounds described in U.S. Patent 3,905,815, Japanese Patent Publication No. 4605/1971, and Japanese Patent Laid-Open Nos. 36281/1973, 32070/1980, 239736/1985, 169835/1986, 169837/1986, 58241/1987, 212401/1987, 70243/1988, and 298339/1988; the organometallic compound/organic halide combinations described in K. Meier et al., *J. Rad. Curing*, 13 (4), 26 (1986), T.P. Gill et al., *Inorg. Chem.*, 19, 3007 (1980), D. Astruc, *Acc. Chem. Res.*, 19 (12), 377 (1896), and Japanese Patent Laid-Open No. 161445/1990; the photo-acid generators having an o-nitrobenzyl type protective group described in S. Hayase et al., *J. Polymer Sci.*, 25, 753 (1987), E. Reichman et al., *J. Polymer Sci.*, *Polymer Chem. Ed.*, 23, 1 (1985), Q.Q. Zhu et al., *J. Photochem.*, 36, 85, 39, 317 (1987), B. Amit et al., *Tetrahedron Lett.*, (24) 2205 (1973), D.H.R. Barton et al., *J. Chem Soc.*, 3571 (1965), P.M. Collins et al., *J. Chem. Soc.*, Perkin I, 1695 (1975), M. Rudinstei et al., *Tetrahedron Lett.*, (17), 1445 (1975), J.W. Walker et al., *J. Am. Chem. Soc.*, 110, 7170 (1988), S.C. Busman et al., *J. Imaging Technol.*, 11 (4), (1985), H.M. Houlihan et al., *Macromolecules*, 21, 2001 (1988), P.M. Collins et al., *J. Chem. Soc., Chem. Commun.*, 532 (1972), S. Hayase et al., *Macromolecules*, 18, 1799 (1985), E. Reichmanis et al., *J. Electrochem. Soc., Solid State Sci. Technol.*, 130 (6), F.M. Houlihan et al., *Macromolecules*, 21, 2001 (1988), European Patents 0,290,750, 046,083, 156,535, 271,851, and 0,388,343, U.S. Patents 3,901,710 and 4,181,531, and Japanese Patent Laid-Open Nos. 198538/1985 and 133022/1978; compounds which photodecompose to generate a sulfonic acid and are represented

by the iminosulfonates and the like described in Tunooka et al., *Polymer Preprints*, Japan, 35 (8), G. Berner et al., *J. Rad. Curing*, 13 (4), W.J. Mijs et al., *Coating Technol.*, 55 (697), 45 (1983), Akzo, H. Adachi et al., *Polymer Preprints*, Japan, 37 (3), European Patents 0,199,672, 84,515, 199,672, 044,115, and 0,101,122, U.S. Patents 4,618,554, 4,371,605, and 4,431,774, and Japanese Patent Laid-Open Nos. 18143/1989, 245756/1990, and 140109/1991; and the disulfone compounds described in Japanese Patent Laid-Open No. 166544/1986.

*Please amend the paragraph at page 84, line 10, as follows:*

The positive type lithographic printing plate precursor of Example 8 thus obtained was exposed to a PS light through a step guide manufactured by Fuji Photo Film Co., Ltd., and then processed by an automatic processor containing developer DP-4 (1:8), manufactured by Fuji Photo Film Co., Ltd. Subsequently, printing was conducted with Heidel Heidelberg printing press KOR-D. As a result, 5,000 satisfactory printed sheets were obtained in which the nonimage areas were free from soils.

*Please amend the paragraph at page 87, line 1, as follows:*

[Composition of Image-Forming Layer]

A composition consisting of 0.1 g of IRG22 (IR dye manufactured by Nippon Kayaku Co., Ltd.), 0.21 g of the crosslinking agent A, 2.1 g of a phenol-formaldehyde novolac (weight-average molecular weight, 12,000), 0.02 g of diphenyliodonium 9,10-dimethoxyanthracenesulfonate, 0.06 g of Megafas Megaface F-176 (fluorochemical surfactant manufactured by Dainippon Ink & Chemicals, Inc.), 15 g of

methyl ethyl ketone, and 12 g of 2-methoxy-1-propane was applied to the same support as in the Examples given above. Thus, a negative type heat-sensitive lithographic printing plate precursor of Example 13 was obtained.

*Please amend the paragraph at page 87, line 13, as follows:*

The negative type lithographic printing plate precursor of Example 13 thus obtained was exposed with a semiconductor laser (wavelength, 825 nm; beam diameter,  $1/e^2 = 6 \mu\text{m}$ ) as a heat mode laser at a linear velocity of 8 m/sec and a plate surface output of 110 mW. After the exposure, the printing plate precursor was heat-treated at 110°C for 1 minute and then processed by an automatic processor containing developer DP-4 (1:8) and rinse FR-3 (1:7), both manufactured by Fuji Photo Film Co., Ltd. Subsequently, the plate surface was treated with gum GU-7 (1:1), manufactured by Fuji Photo Film Co., Ltd. Printing was conducted with Heidel Heidelberg printing press KOR-D. As a result, 6,000 printed sheets were obtained in which the nonimage areas were free from soils.